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Elucidation of Anchoring and Restructuring Steps during Synthesis of Silica-Supported Vanadium Oxide Catalysts

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Supporting Information

ABSTRACT: We investigate the chemical reactions involved during the synthesis of supported vanadium oxide catalysts using chemical grafting of vanadium oxytriisopropoxide $(VO(O^{i}Pr)_{3})$ to thermally pretreated silica under solvent-free conditions. $VO(O'Pr)_3$ is found to react with both site-isolated silanol (Si-OH) groups and strained siloxane (\equiv Si−O−Si≡) bridges at the silica surface. Solid-state ⁵¹V and ¹³C MAS NMR confirms the formation of two slightly different vanadium species associated with the two anchoring mechanisms. In situ diffuse reflectance infrared Fourier



transform spectroscopy (DRIFTS), in situ Raman spectroscopy, and thermogravimetric analysis-differential scanning calorimetry-mass spectrometry (TGA-DSC-MS) were used to study the subsequent calcination, revealing the formation of a transient V-OH intermediate upon the release of propene, followed by the formation of isolated VO4 surface species upon elimination of water. X-ray absorption spectroscopy (XAS) and ⁵¹V MAS NMR of the calcined material confirm the conversion of the two original vanadium sites to a species with a single isotropic shift, confirming the formation of isolated, tetrahedral VO_4 sites.

INTRODUCTION

Supported metal oxide catalysts, such as supported vanadium oxide, facilitate a variety of important chemical transformations including selective oxidations¹ and reductions.^{2,3} The precise nature of the metal oxide surface structure ultimately dictates the catalytic activity of the material. For example, a supported vanadium oxide catalyst composed of only dispersed vanadium oxide species (i.e., submonolayer metal oxide sites bound directly to the support surface) will often result in different catalytic reactivity than a catalyst that also contains supported V₂O₅ nanoparticles. The oxidative dehydrogenation of propane (ODHP) reaction can be taken as a case study in this context.¹ Supported vanadium oxide catalysts containing only dispersed vanadium oxide species favor the direct dehydrogenation pathway to propene, whereas catalysts containing V2O5 nanoparticles accelerate the rate of overoxidation of propene to CO_{xy} thus lowering selectivity to propene.⁴ In an effort to elucidate such structure-reactivity relationships, the nature of the supported vanadium oxide species has been rigorously investigated by a number of techniques such as UV-visible spectroscopy,^{5–8} Raman spectroscopy,^{7–11} Infrared (IR) spectroscopy,^{6,7} X-ray absorption spectroscopy (XAS),^{7,12-14} and solid-state NMR.9,15-19 The focus of the characterization studies listed above is largely toward understanding the

structure of the material, under a wide variety of conditions. However, as an alternative approach, a molecular-level understanding of the controlling chemistry during surface functionalization could serve to improve the material synthesis, e.g., to maximize the formation of desired supported metal oxide sites and/or to immobilize different metal oxides with molecular precision using scalable technology.

To a large extent, choice of synthesis procedure influences the type of vanadium oxide surface structure of the final supported catalyst.⁴ Common synthesis procedures for these materials include (i) solution-based techniques such as wet impregnation and ion exchange,^{4,20,21} and (ii) deposition techniques such as chemical grafting^{13,14,22–26} and atomic layer deposition (ALD).²⁷⁻³⁰ In each of these synthesis techniques, a vanadium precursor is introduced to an oxide support material. In most cases (with the exception of a few of the mentioned grafted materials^{13,22-24}), the initial functionalization is followed by calcination at high temperatures (>500 °C) in order to eliminate the native metal precursor ligands and form the supported metal oxide surface species.

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Among the different preparation methods for supported metal oxides, grafting has shown versatility as a technique to monitor the transformation of the metal oxide precursor to dispersed metal oxide surface species.^{23,24,31,32} Grafting, along with other vapor-phase deposition techniques like ALD, enable better control over the dispersion of metal oxides sites compared to wet impregnation due to the fact that anchoring of the metal precursor is limited to the number of initially available chemisorbing anchoring sites on the support.³³ In the case of silica-supported materials, the number of anchoring sites available during grafting is often controlled by the thermal pretreatment of silica.^{13,23,24,26,31,32} Thermal pretreatment controls the average surface density of silanol (Si-OH) groups, generally assumed to be the predominant anchoring points on the support. Depending on the metal precursor used, strained siloxane (\equiv Si-O-Si \equiv) bridges generated during the dehydration of silica at high temperatures can also act as anchoring sites during grafting. 31,32,3

In the present contribution, we investigate the anchoring and subsequent thermal reconstruction of vanadium oxide on amorphous silica as a representative case study for the steps governing the formation of supported metal oxide sites. We synthesized silica-supported vanadium oxide via the solvent-free vapor deposition of VO(O'Pr)₃ to silica dehydrated at 700 °C $(SiO_{2(700)})$. This particular vanadium precursor was chosen due to its wide use in both solution and deposition-based synthesis procedures for supported vanadium oxide. To gain insights into the elementary anchoring and restructuring steps during functionalization of the silica support, we characterized the structure of the vanadium sites on the silica support before, during, and after calcination. The surface sites on the initially grafted material (V/SiO_{2(700)}) were characterized using a combination of transmission FT-IR spectroscopy, X-ray absorption near edge structure (XANES) analysis, and solidstate $^{13}\mathrm{C}$ and $^{51}\mathrm{\breve{V}}$ magic angle spinning (MAS) NMR spectroscopy. These same techniques were also applied to VO(OⁱPr)₃ grafted on a presilvlated support (V/TMS- $SiO_{2(700)}$) in order to investigate specifically the anchoring of the vanadium precursor to strained siloxane bridges. The conversion of grafted vanadium sites to their final, metal oxide surface structures was monitored using various in situ techniques, including diffuse reflectance infrared Fourier transform spectroscopy (DRIFTS), Raman spectroscopy, and thermogravimetric analysis-differential scanning calorimetrymass spectrometry (TGA-DSC-MS). The vanadium structure on the grafted, calcined material and its presilylated counterpart (V/SiO₂₍₇₀₀₎-O₂ and V/TMS-SiO₂₍₇₀₀₎-O₂, respectively) were characterized with a combination of solid-state ⁵¹V MAS NMR, and XANES analyses. In addition, V/SiO₂₍₇₀₀₎-O₂ was also tested for the ODHP reaction as a probe reaction to both demonstrate the catalytic applicability of this grafted material and to verify the sole presence of dispersed, two-dimensional vanadium oxide species. Precisely synthesized materials, such as the supported vanadium oxide system described in this work, represent "model" catalyst systems that can be used toward understanding the structure and dispersion of surface species on a wider library of supported materials.

EXPERIMENTAL SECTION

Materials Synthesis. Silica powder (Aerosil 200 from Degussa, specific surface area of 200 m²·g⁻¹) was impregnated with water and dried overnight at 100 °C in a vacuum oven. Afterward, the material was dehydrated at 200–800 °C (16 h) at 15 μ bar dynamic vacuum

and stored inside a glovebox (<1 ppm of O_2 and H_2O) in order to avoid readsorption of water. These materials are denoted as $SiO_{2(X)}$, with X referring to the dehydration temperature.

VO(OⁱPr)₃ (Sigma-Aldrich, distilled two times before use, colorless) was deposited onto 300 mg of thermally pretreated silica (10 equiv based on initial silanol content) at ca. 20 μ bar dynamic vacuum. The transfer phase (1 h) was followed by a reaction phase at room temperature (30 min) and a mild thermal post-treatment at 50 °C and 20 μ bar dynamic vacuum (1 h) in order to evaporate the excess of VO(OⁱPr)₃ (material denoted as V/SiO_{2(X)}). Samples were subsequently calcined in an air flow at 600 °C for 3 h (material denoted as V/SiO₂₍₇₀₀₎-O₂) and dehydrated for further use (300 °C, 3 h, 20 μ bar dynamic vacuum).

N,*N*-Bis(trimethylsilyl)methylamine, or $(TMS)_2NMe$, (Sigma-Aldrich, distilled two times before use) was used for the silylation of the dried silica (material denoted as TMS-SiO_{2(X)}). The silylating agent was exposed to the dried silica under 20 µbar vacuum in the same way as VO(OⁱPr)₃ (using 5 equiv based on initial silanol content) and thermally post-treated at 250 °C. Afterward, VO(OⁱPr)₃ was deposited on the silylated material to obtain V/TMS-SiO_{2(X)} (5 equiv based on initial silanol content).

Materials Characterization. The vanadium content was quantified with ICP-OES (Optima 2000 DV from PerkinElmer) after digestion of the samples in HF.

Infrared spectra were recorded on a self-supporting wafer using a Bruker Alpha spectrometer in transmission mode (resolution of 2 cm⁻¹). Intensities were normalized to the Si–O–Si overtones of the silica framework. Analysis was carried out inside a glovebox (<1 ppm of H_2O and O_2).

The DRIFTS spectra were recorded by averaging 32 scans with a resolution of 8 cm⁻¹. The DiffusIR accessory (PIKE Technologies) was flushed with synthetic air at a flow rate of ca. 20 mL min⁻¹ and heated at a heating rate of 20 °C·min⁻¹ up to a temperature of 600 °C. The DRIFTS sample holder was filled and sealed in a glovebox (<1 ppm of O₂ and H₂O) prior to measurement.

Solid-state ¹³C NMR and ⁵¹V-NMR spectra were acquired on an Avance IIIHD NMR spectrometer (Bruker) operating at a ¹H Larmor frequency of 400 MHz. The samples were spun around the magic angle with a rate of 18 kHz at room temperature using $N_2(g)$ for the drive, bearing and VT flow. A double resonance 3.2 mm probe (with the rotor containing ca. 15 mg sample) was tuned to 100.64 or 105.22 MHz for the ¹³C and ⁵¹V experiments, respectively. The ppm scale of the spectra was calibrated using the ¹³C signal of adamantane as an external secondary reference. All samples were packed into rotors inside a glovebox (<1 ppm of O₂ and H₂O).

Thermogravimetric analysis-differential scanning calorimetry of the calcination step was performed using a TGA-DSC Thermobalance (LINSEIS) in combination with an OmniStarTM mass spectrometer (Pfeiffer Vacuum). V/SiO₂₍₇₀₀₎ (ca. 10 mg) was sealed in an aluminum sample pan inside a glovebox (<1 ppm of O₂ and H₂O) prior to TGA-DSC-MS analysis.

In situ Raman measurements were carried out with a Renishaw InVia Raman Spectrometer with a 785 nm excitation laser. All measurements used a 1200 l mm⁻¹ grating and were taken with a range of 250–1200 cm⁻¹ and a dispersion of 1.36565 cm⁻¹ pixel⁻¹. Prior to calcinations, samples were loaded and sealed in a high-temperature Linkam CCR1000 cell inside a glovebox (<1 ppm of O₂ and H₂O) prior to measurement.

X-ray absorption near-edge structure (XANES) spectra were obtained at the V K-edge (5465.1 eV) using bending magnet station B at sector 20 of the Advanced Photon Source beamline (20-BM-B) at Argonne National Laboratory. The beam energy and detector were calibrated to the V K-edge using pure vanadium foil in transmission mode. The beam energy was controlled using a Si(111) monochromator with 1.4×10^{-4} eV resolution. Samples were pressed into a self-supporting wafer inside a helium atmosphere glovebox (<1 ppm of O₂ and H₂O), and the sample holder was sealed in a quartz tube fitted with Kapton windows on either end. All spectra were collected in transmission mode.

Catalytic Testing. Catalytic activity measurements were performed using a Microactivity-Effi reactor. 80 mg of catalyst (particle size of 600–710 μ m) was mixed with inert SiC particles of equal size in a ratio of 2:1 (SiC-to-catalyst) and packed inside a quartz reactor tube (9 mm ID). Reactions were carried out at 490 °C with inlet flow ratios of 3:6:11 O₂:C₃H₈:N₂. Exhaust streams were analyzed using a Shimadzu 2010 GC equipped with three Restek columns (Rtx-1, Rt-Q-Bond and RT-Msieve 5A) and a Thermal Conductivity Detector (TCD) and Flame Ionization Detector (FID). The catalysts were investigated under different contact times to monitor product selectivity at varying propane conversions (inverse weight-hourspace-velocity (WHSV⁻¹) of 40–130 [kg-cat s m⁻³]). The carbon balance closes within 2%.

RESULTS AND DISCUSSION

Grafting VO(OⁱPr)₃ **to Dehydrated Silica.** Prior to grafting VO(OⁱPr)₃, the silica support was dehydrated under dynamic vacuum (ca. 20 μ bar) at various temperatures (i.e., 200, 500, 600, 600, 700, and 800 °C). During the grafting step, the liquid vanadium precursor VO(OⁱPr)₃ was transferred under vacuum in the vapor phase and condensed onto SiO_{2(X)} at -78 °C. The material was warmed to room temperature and then thermally post-treated at 50 °C under dynamic vacuum to remove excess precursor. The structural changes occurring during thermal dehydration of silica and during the subsequent grafting were investigated using transmission infrared (IR) spectroscopy, as summarized in Figure 1.



Figure 1. Transmission infrared spectra of silica dehydrated at 200, 500, 600, 700, and 800 °C ($SiO_{2(200)}$, $SiO_{2(500)}$, $SiO_{2(600)}$, $SiO_{2(700)}$, $SiO_{2(800)}$, respectively), silylated $SiO_{2(700)}$ (TMS- $SiO_{2(700)}$), $VO(O'Pr)_3$ grafted to silylated $SiO_{2(700)}$ (V/TMS- $SiO_{2(700)}$), $VO(O'Pr)_3$ grafted to $SiO_{2(200)}$ (V/SiO₂₍₂₀₀₎) and to $SiO_{2(700)}$ (V/SiO₂₍₇₀₀₎), and $VO(O'Pr)_3$ precursor diluted in KBr.

The IR spectrum of the silica support dehydrated at 200 °C under vacuum exhibits a sharp signal at 3740 cm⁻¹ and a broad shoulder around 3666 cm⁻¹ (Figure 1, SiO₂₍₂₀₀₎). These two features are attributed to isolated and hydrogen bonded silanols, respectively.³⁵ The broad spectral features between 1500 and 2000 cm⁻¹ in Figure 1 correspond to framework Si–O–Si overtones that were used to normalize the intensities of the different silica spectra. Upon thermal treatment under vacuum at temperatures above 600 °C, the IR spectrum of silica only shows a sharp signal at 3748 cm⁻¹, indicating that SiO₂₍₇₀₀₎

and SiO₂₍₈₀₀₎ feature predominantly noninteracting silanol (SiOH) groups (Figure 1, inset), in addition to a small fraction (~5%) of geminal diols that exhibit a similar IR signature (within 2 cm⁻¹) to the isolated silanol signal.^{35–37} After VO(OⁱPr)₃ is exposed to the SiO₂₍₇₀₀₎ support (material denoted as V/SiO₂₍₇₀₀₎), the infrared spectrum shows several bands in the 2850 to 3000 cm⁻¹ range, whereas the signal at 3748 cm⁻¹ is completely consumed. From the latter, we infer that the vanadium precursor reacts quantitatively with the isolated surface silanol groups, substituting an alkoxide on the original VO(OⁱPr)₃ vanadium precursor for a siloxide ligand according to reaction 1.

$$\equiv \text{SiOH} + \text{VO}(\text{O}^{i}\text{Pr})_{3} \rightarrow \equiv \text{SiO} - \text{VO}(\text{O}^{i}\text{Pr})_{2} + {}^{i}\text{PrOH}$$
(1)

This proposed reaction is in line with studies conducted by Guillemot and co-workers, who observe the release of isopropyl alcohol by NMR spectroscopy for the anchoring reaction of $VO(O^{i}Pr)_{3}$ to a model silanol-functionalized polytungstate system.³⁸ Grafting to $SiO_{2(200)}$ reveals that the H-bonded SiOH groups are significantly less reactive than the isolated SiOH groups, as evidenced by the fact that the broad peak corresponding to the O–H stretch for hydrogen bonded silanols still remains in the IR spectrum for V/SiO₂₍₂₀₀₎ (Figure 1).

In the IR spectra of $VO(O^{i}Pr)_{3}$ -functionalized materials in Figure 1, the bands between 2850 and 3000 cm⁻¹ correspond to the C-H stretches originating from the isopropoxide ligands. Comparison of the C-H stretch fingerprint for the $V/SiO_{2(700)}$ material with the spectrum of the $VO(O'Pr)_3$ precursor reveals a difference in the relative intensities of these bands. This suggests that more complex chemistry than only that illustrated in reaction 1 might be taking place. On the basis of the isolated silanol density of $SiO_{2(700)}$ of ca. 0.9 $nm^{-239,40}$ and the determined BET surface area of ca. 186 ± 6 $m^2 \cdot g^{-1}$, one would expect, based on a simple 1:1 stoichiometry of $VO(O^{i}Pr)_{3}$ with SiOH groups, a vanadium loading of ca. 1.5 wt %. However, bulk analysis of the V/SiO₂₍₇₀₀₎ sample indicates a vanadium loading of 2.9 \pm 0.3 wt %. One plausible explanation for this anomaly is that $VO(O^{i}Pr)_{2}$ reacts not only with surface silanols but also with (strained) siloxane bridges $(\equiv Si - O - Si \equiv)$ at the silica surface, that arise as a consequence of dehydration at high temperatures under vacuum. We emphasize that the peak intensities in the C-H stretching region for the $V/SiO_{2(200)}$ material resemble the $VO(O^{i}Pr)_{3}$ precursor more closely than V/SiO₂₍₇₀₀₎, and that $V/SiO_{2(200)}$ features less strained siloxane bridges, due to the lower pretreatment temperature.³⁵

To verify further the hypothesis that the VO(OⁱPr)₃ precursor reacts with both silanol groups and siloxane bridges, we silylated SiO₂₍₇₀₀₎, viz, conversion of \equiv SiOH groups to \equiv SiOSi(CH₃)₃ (material denoted as TMS-SiO₂₍₇₀₀₎), prior to grafting VO(OⁱPr)₃. After SiO₂₍₇₀₀₎ is exposed to the silylating agent *N*,*N*-bis(trimethylsilyl)methylamine ((TMS)₂NMe) under vacuum, the surface silanols are indeed capped with nonreactive trimethylsilyl (TMS) groups, as verified by IR spectroscopy (Figure 1, "grafted materials"). We emphasize that no nitrogen impurities could be detected with X-ray photoelectron spectroscopy (XPS), excluding a significant reaction of (TMS)₂NMe with the siloxane bridges, as well as the presence of physisorbed silylating agent. We therefore conclude that when exposed to the TMS-SiO₂₍₇₀₀₎ support, VO(OⁱPr)₃ can only react with surface siloxane bridges, as the material has a



Figure 2. (a) ⁵¹V MAS NMR spectra of V/SiO₂₍₇₀₀₎ (top) and V/TMS-SiO₂₍₇₀₀₎ (bottom), with proposed assignments for signals 1 and 2. (b) ¹³C MAS NMR of V/SiO₂₍₇₀₀₎ (top) and V/TMS-SiO₂₍₇₀₀₎ (bottom), with proposed assignments for signals 1', 2', and 3' observed in both spectra (* Indicates the ¹³C signal associated with TMS groups in the V/TMS-SiO₂₍₇₀₀₎ sample introduced during the silylation).

vanadium loading ca. 0.9 ± 0.2 wt %. From this experiment, we conclude that $VO(O^{i}Pr)_{3}$ can anchor to the surface of silica without the presence of silanol groups. Therefore, we interpret the anomaly in vanadium loading for $V/SiO_{2(700)}$ as evidence for the direct reaction of the $VO(O^{i}Pr)_{3}$ precursor with (strained) siloxane bridges in addition to isolated silanol groups.

In contrast to the direct reaction of $VO(O^{i}Pr)_{3}$ with siloxane bridges, we also consider two indirect pathways in which the anchoring of VO(O'Pr)₃ to siloxane bridges could occur. First, the case where the isopropyl alcohol released in reaction 1 reacts with siloxane bridges to form additional silanol grafting sites can be excluded for the case where $VO(O'Pr)_3$ is grafted to TMS-SiO₂₍₇₀₀₎. This is due to the lack of proton source on TMS-SiO₂₍₇₀₀₎ to protonate the isopropoxide ligands of the precursor, and therefore no proton source in which to subsequently open the siloxane bridges present on the surface. The second indirect pathway to open siloxane bridges during grafting could be the Lewis acid-catalyzed reaction of the isopropanol formed during reaction 1 with the siloxane bridges in the presence of additional $VO(O^{i}Pr)_{3}$ precursor. An analogous mechanism was also previously suggested for the grafting of tin precursor $Sn(NMe_2)_4$ to $SiO_{2(700)}^{31}$. The Lewis acid-catalyzed mechanism, of course, would only be plausible on $SiO_{2(700)}$ where protons are available from the surface SiOH groups. However, the vanadium-loading of V/TMS-SiO₂₍₇₀₀₎ (where only the direct reaction of $VO(O'Pr)_3$ with siloxane bridges is likely) matches the discrepancy between the vanadium-loading of V/SiO₂₍₇₀₀₎ and the calculated vanadiumloading that should result from quantitative reaction of $VO(O'Pr)_3$ with isolated silanols (ca. 1.5 wt % V; vide supra). This illustrates that grafting to siloxane bridges occurs without the presence of protons and that a Lewis acid-catalyzed pathway is thus not likely to occur for the reaction of $VO(O'Pr)_3$ with siloxane bridges.

The aforementioned experiments lead us to a first important conclusion: dispersion of vanadium oxide does not only depend on the silanol groups but also on the more hydrophobic siloxane bridges on the silica surface.

Structural Characterization of V/SiO₂₍₇₀₀₎ and V/TMS-SiO₂₍₇₀₀₎ with Solid-State NMR and XANES. We investigate the structure of the vanadium species on V/SiO₂₍₇₀₀₎ and V/TMS-SiO₂₍₇₀₀₎ using solid-state ⁵¹V and ¹³C MAS NMR (Figure 2a,b, respectively). The ⁵¹V MAS NMR spectra for both V/SiO₂₍₇₀₀₎ and V/TMS-SiO₂₍₇₀₀₎ feature two signals with

shifts centered at -630 ppm (1) and -655 ppm (2). The overall lower signal intensity for the V/TMS-SiO₂₍₇₀₀₎ sample compared to V/SiO₂₍₇₀₀₎ is due to the difference in vanadium loading (vide supra). Signal 2 has significant spinning sidebands whereas signal 1 has virtually none. Fitting of the experimental spectra furthermore reveals that signal 1 has a line width of ca. 1 kHz whereas the line width of signal 2 is twice as large at ca. 2.3 kHz (see Supporting Information Figure S1 and Table S1). In addition, the fit of signal 2 reveals that it has a significantly larger Quadrupole Coupling Constant (QCC) compared to signal 1 (Table S1). It is the quadrupolar interaction that is responsible for the appearance of the spinning sidebands, as neither signal displays a significant chemical shift anisotropy. This suggests that the species associated with signal 1 are significantly more symmetric than the species that give rise to signal 2. The lower ratio of signal 1 to signal 2 for V/TMS-SiO₂₍₇₀₀₎ compared to V/SiO₂₍₇₀₀₎ points toward a different site speciation that is likely due to different anchoring mechanisms that arise from the difference in available anchoring points on the $\text{SiO}_{2(700)}$ and $\text{TMS-SiO}_{2(700)}$ supports. It is important to note that the ratio of intensities between peaks 1 and 2 in these spectra give only qualitative information about the speciation differences between V/SiO₂₍₇₀₀₎ and V/TMS-SiO₂₍₇₀₀₎. To achieve a truly quantitative picture of the site speciation for 1 and 2 on each material, the total integrations of these spectra would have to be normalized to a known reference (such as V_2O_5) and the spectral intensities scaled to sample weight and number of acquisition scans, as has been demonstrated, for example, by Peden and co-workers on titanium nanorodsupported vanadium oxide.¹⁹

We assign signal 1 the to monopodal, freely rotating \equiv SiO-VO(OⁱPr)₂ species 1 (see Figure 2a). The narrow line width of peak 1, combined with the fact that there is a negligible electric field gradient at the ⁵¹V nucleus for this species. The fact that there are virtually no spinning sidebands associated with this peak means that both the quadrupole interaction and the chemical shift anisotropy are rather small, which can be explained by a dynamic environment (i.e., more rotational freedom) around the ⁵¹V nucleus. We postulate that this species arises predominantly from reaction of VO(OⁱPr)₃ with isolated SiOH groups, as the relative abundance of species 1 is significantly higher in the V/SiO₂₍₇₀₀₎ sample.

The spinning sidebands associated with peak **2** indicate that this peak experiences an electric field gradient at the location of the ⁵¹V nucleus and hence exhibits a significant QCC. It is a clear indication of a less symmetric environment. The chemical shift anisotropy is, however, almost absent. On the basis of this lower symmetry, as well as the minor upfield shift by 25 ppm compared to signal 1, we attribute signal 2 to a structure where the vanadium center features a weak fifth coordination bond to an adjacent \equiv Si-O'Pr moiety (species 2 in Figure 2a). This perturbs the tetrahedral geometry of the vanadium site into a distorted square-pyramidal structure, whose asymmetric coordination environment is responsible for the intensity of the spinning sidebands associated with signal 2. We postulate the magnitude of the QCC (888 kHz) in combination with negligible chemical shift anisotropy strongly supports the presence of a weak interaction for species 2: there is sufficient rotational averaging in this species to average out contributions from chemical shift anisotropy; however, the interaction of the ⁵¹V nucleus with the adjacent \equiv Si-OⁱPr site reduces the symmetry about the ⁵¹V nucleus to the point where strong quadrupolar interactions (responsible for the spinning sidebands) are still prevalent. In addition, we emphasize that the additional weak coordination bond slightly increases the electron density at the vanadium nucleus, causing the subtle shielding effect compared to signal 1. As the relative abundance of peak 2 is much higher in the silvlated material V/TMS- $SiO_{2(700)}$, we assume that species 2 is mainly formed in the reaction of VO(O'Pr)₃ with strained siloxane bridges.

Alternative structures that would feature a high degree of anisotropy (either quadrupolar or chemical shift), and could hence potentially explain signal 2 in the ⁵¹V NMR spectra, are the two bipodal species in Scheme 1 (labeled **2bis** and **2tris**).

Scheme 1. Possible Structures for the Species Experimentally Observed in $^{51}\mathrm{V}$ MAS NMR^a



^{*a*}From left to right: monopodal species **1**, distorted monopodal vanadium species with a weak fifth coordination to an adjacent $Si-O^{i}Pr$ moiety (species **2**), bipodal vanadium with two surface Si-O-V bonds (= $Si(OH)_2$; species **2bis**), and geminal bipodal vanadium species that could arise from subsequent grafting to geminal (> $Si(OH)_2$) silanol groups (species **2tris**).

Indeed, the anchoring of one VO(OⁱPr)₃ molecule to two isolated silanols at sufficiently close proximity to one another would yield the (\equiv SiO)₂VO(OⁱPr) species **2bis**. In addition, approximately 5% of the silanols on SiO₂₍₇₀₀₎ are present as geminal diols,³⁵ and grafting to those >Si(OH)₂ groups could yield the >SiO₂VO(OⁱPr) species **2tris**. Although the former seems unlikely at a silanol surface coverage of only 0.9 nm⁻² for SiO₂₍₇₀₀₎, local deviations from a pure statistical distribution could indeed cause the formation of such bipodal species. However, we emphasize that such mechanisms are not possible in the absence of silanols, and that signal **2** is also observed, and even in a higher relative abundance to signal **1**, on V/TMS-SiO₂₍₇₀₀₎, where all silanols on the support are capped on the TMS-SiO₂₍₇₀₀₎ support prior to grafting. In addition, the fact that only quadrupolar interaction (and no chemical shift anisotropy) is observed for signal 2 in ⁵¹V NMR does not support the presence of species **2bis** or **2tris**. Both species **2bis** and **2tris** have two surface bonds to silica, meaning that elimination of contributions from chemical shift anisotropy via rotational averaging is virtually impossible. **2bis** and **2tris** would likely have significant contributions from both chemical shift anisotropy and quadrupolar coupling, which would manifest itself in much more pronounced spinning sidebands, such as those observed for dispersed vanadium oxide species on silica after calcination.¹⁸

The ¹³C MAS NMR spectra for V/SiO₂₍₇₀₀₎ and V/TMS-SiO₂₍₇₀₀₎ in Figure 2b share three chemical shifts at 85 ppm (1'), 67 ppm (2'), and 25 ppm (3'). V/TMS-SiO₂₍₇₀₀₎ also has a peak at -0.86 ppm arising from surface TMS groups. The signal at 25 ppm corresponds to primary methyl groups in the isopropoxide ligands. Signals 1' and 2' are in the chemical shift range of the tertiary carbon directly bound to the oxygen in the isopropoxide ligand and are assigned to V-OⁱPr and Si-OⁱPr, respectively, based on the deshielding expected for the V-OⁱPr tertiary carbon relative to the Si-OⁱPr tertiary carbon. The Si-OⁱPr species most likely arise from transfer of one of the VO(OⁱPr)₃ isopropoxide ligands to the silica surface during grafting to siloxane bridges (see Scheme 2). These ¹³C NMR

Scheme 2. Possible Reactions of the $VO(O^iPr)_3$ Precursor with Isolated Silanol and Siloxane Bridge Sites, Respectively



spectra also allow us to further reject the bipodal structures hypothesized in Scheme 1. Indeed, if we assume that the two tertiary carbon signals from the Si–OⁱPr and V–OⁱPr moieties (signals 1' and 2', Figure 2b) have a similar extinction coefficient due to their similar chemical environment, integration of these two peaks allows us to estimate their relative abundance at ca. 2:1 for the V/TMS-SiO₂₍₇₀₀₎ material. This observation is only consistent with the formation of the distorted square-pyramidal structure 2 in Scheme 1. Indeed, in both bipodal cases drawn in Scheme 1, the vanadium site only contains one isopropoxide ligand; whereas in case of the distorted square-pyramidal species, the vanadium site maintains two native isopropoxide ligands in addition to one \equiv Si–OⁱPr species.

The assignment of signals 1 and 2 in ⁵¹V MAS NMR also agrees with analysis of the XANES region of the XAS spectra reported in the Supporting Information (Figure S2, panel a). Indeed, the normalized pre-edge in the XANES spectra of the vanadium K-edge can be correlated with the local environment of vanadium. The normalized XANES region for V/SiO₂₍₇₀₀₎, V/TMS-SiO₂₍₇₀₀₎, and reference material VO(OSiPh₃)₃ all have pre-edge transitions at approximately 5469 eV. On the basis of the combination of XANES and ⁵¹V MAS NMR analyses, we postulate the vanadium sites on V/SiO₂₍₇₀₀₎ and V/TMS-SiO₂₍₇₀₀₎ have predominantly tetrahedral geometry. However, although the energy of the pre-edge peak is effectively the same for V/SiO₂₍₇₀₀₎ and VO(OSiPh₃)₃, the normalized absorption intensity of the pre-edge peak is higher for V/TMS-SiO₂₍₇₀₀₎. We attribute this increase in intensity to an increase in the quadrupolar coupling of the vanadium nuclei, which in turn reflects the more asymmetric environment of vanadium in the silvlated sample. This supports the conclusions drawn from the ⁵¹V MAS NMR studies, which show a much higher relative abundance of the asymmetric species 2 (with a higher quadrupolar coupling constant) for the V/TMS-SiO₂₍₇₀₀₎ material. Although the intensity of the normalized pre-edge peak for V/TMS-SiO₂₍₇₀₀₎ is higher, the peak position does not shift. This observation appears to indicate that although the vanadium sites, on average, are in a more distorted configuration, they remain predominantly tetrahedrally coordinated. On the other hand, if the local environment of vanadium restructured into a truly pentacoordinated configuration, the intensity of the pre-edge peak would decrease, rather than increase.41 All of these observations are in line with the proposed vanadium structure 2 in Scheme 1.

We now return to the observation that both the symmetric (signal 1) and asymmetric (signal 2) species are observed with 51 V NMR on V/TMS-SiO₂₍₇₀₀₎ (see Figure 2a). To investigate this in more detail, we grafted vanadium to silylated silica that was pretreated at different temperatures (500–800 °C). From the 51 V NMR spectra displayed in Figure 3, one can conclude



Figure 3. ^{51}V MAS NMR spectra of V/TMS-SiO $_{2(500)}$, V/TMS-SiO $_{2(600)}$, V/TMS-SiO $_{2(700)}$, and V/TMS-SiO $_{2(800)}$.

that the relative abundance of previously assigned species 1 and 2 changes drastically with dehydration temperature. These observations point toward the almost exclusive formation of asymmetric vanadium species of type 2 on the silylated silica pretreated at temperatures up to 600 °C. At higher pretreatment temperatures, more symmetric (tetrahedral) vanadium species of type 1 are generated, in addition to the type 2 species. Clearly, the coordination environment of the grafted vanadium species is very sensitive to the changes in the silica surface that occur during thermal treatment. This effect correlates with the formation of more strained siloxane bridges at higher pretreatment temperatures (>600 °C), due to more

extensive dehydroxylation of the surface hydroxyl species.³⁵ The more strained siloxane bridges seem to react with the $VO(O^{i}Pr)_{3}$ precursor to form the isolated tetrahedral sites, and react in such a way as to minimize ring strain on the silica surface.

From this series of solid-state NMR and XANES studies, we conclude that the grafting of $VO(O^{i}Pr)_{3}$ to silica leads to the formation of two types of surface species, one monopodal species (1, Figure 1a) that is tetrahedral and one distorted tetrahedral species with a fifth additional weak interaction with a neighboring \equiv Si $-O^{-i}Pr$ group (2, Figure 2a). When grafting to siloxane bridges only, the relative abundance of species 1 and 2 depends on the pretreatment temperature of the silica.

Thermal Restructuring of Vanadium Sites During Calcination of V/SiO₂₍₇₀₀₎. After the grafting step, V/SiO₂₍₇₀₀₎ was calcined under air flow (20 mL·min⁻¹) at 600 °C to yield the material V/SiO₂₍₇₀₀₎-O₂. This step was monitored using *in situ* DRIFTS. The temperature-dependent IR spectra are displayed in Figure 4. Upon heating, the intensity



Figure 4. In situ DRIFTS study of the calcination of $V/SiO_{2(700)}$ (ramp rate of 20 °C min⁻¹ under air).

of the IR signals from the organic ligands $(2850-3000 \text{ cm}^{-1})$ gradually decreases and eventually vanishes above 400 °C. At approximately 200 °C, signals at 3738 and 3656 cm⁻¹ start to appear which we attribute to SiO–H and VO–H stretches, respectively.⁷ The transient behavior of the VO–H species identifies them as an intermediate in the restructuring process. After completion of the calcination, only trace amounts of the SiO–H signal remain in the IR spectrum.

The calcination of V/SiO₂₍₇₀₀₎ was also monitored using coupled thermogravimetric analysis-differential scanning calorimetry-mass spectrometry (TGA-DSC-MS). Figure 5a overlays the measured mass loss and change in heat flow with respect to temperature during the calcination as measured by TGA and DSC, respectively. At 225–230 °C, a sharp endothermic transition is observed in the DSC trace, and a sharp decrease in mass is observed in the TGA trace. When coupled with the MS data (Figure 5b), it appears that mass fragments corresponding to propene (m/z = 42) and water (m/z = 18) both appear in the temperature range of 225–250 °C.

Complementary information on the calcination process of V/ SiO₂₍₇₀₀₎ was obtained by *in situ* Raman spectroscopy (Figure 6). The results indicate that the V \equiv O (vanadyl) stretch



Figure 5. (a) TGA (right axis) and DSC (left axis) traces as a function of temperature for the calcination of 10 ± 0.1 mg V/SiO₂₍₇₀₀₎ under air. (b) Evolution of the propylene and water signals observed with MS as a function of the calcination temperature.



Figure 6. In situ Raman spectra of $V/SiO_{2(700)}$ during calcination in air, as well as Raman spectra of $V/SiO_{2(700)}$ before and after calcinations, both taken at 25 °C (inset).

characteristic for dispersed vanadium at ca. 1037 cm⁻¹ is preserved throughout the entire calcination.^{10,11} Comparison of the uncalcined V/SiO₂₍₇₀₀₎ and calcined V/SiO₂₍₇₀₀₎-O₂ at room temperature shows a shift in the vanadyl stretch from 1037 to 1044 cm⁻¹, respectively (Figure 6, inset), which is likely due to the slight change in vanadyl stretch environment upon formation of multiple Si-O-V surface bonds during calcination. A Raman shift between 983 and 998 cm⁻¹ was never observed, indicating that no vanadium oxide nanoparticles are generated.^{10,11}

Scheme 3 summarizes our hypothesized pathways by which vanadium sites on $V/SiO_{2(700)}$ restructure upon calcination, based on observations from our DRIFTS, TGA-DSC-MS, and Raman experiments. In the first step, the isopropoxide ligands

from both V–O–^{*i*}Pr and Si–O–^{*i*}Pr moieties decompose to propene (observed by mass spectrometry), which also in turn corresponds to the decrease in organic signal in the DRIFTS spectra. Upon the elimination of propene, Si–OH and V–OH species are formed. A proposed mechanism is given for the formation of V–OH species in which the vanadyl moiety abstracts a proton from an adjacent methyl group. Through a cyclic six-membered transition state, the three carbons from the isopropoxide ligand leave as propene and a V–OH group remains. We emphasize that this mechanism is in line with the observation that the V=O stretch is conserved throughout the calcination process as demonstrated by *in situ* Raman spectroscopy.

In the second step of Scheme 3, the initial surface Si-O-V linkages are formed by via a condensation reaction between nearby V–OH and Si–OH groups formed in the first step outlined in Scheme 3. This is evidenced by the transient behavior of the Si–OH and V–OH species in DRIFTS (Figure S3), as well as by the fact that the release of water is observed in concert with a significant endothermic reaction in the TGA-DSC-MS data (Figure 5). Given the low density of Si–OH groups on the surface during calcination, further Si–O–V linkages are likely formed from the reaction of V–OH groups with adjacent Si–O–Si bridges, which is supported by the fact that Si–OH group roton to open the Si–O–Si linkage) are still observed in DRIFTS at the end of the calcination.

Characterization of Calcined V/SiO₂₍₇₀₀₎-O₂. Both V/ $SiO_{2(700)}$ and V/TMS-SiO_{2(700)} were calcined in air at 600 $^\circ C$ to yield materials denoted V/SiO₂₍₇₀₀₎-O₂ and V/TMS-SiO₂₍₇₀₀₎- O_{2} , respectively. The ⁵¹V MAS NMR spectra of dehydrated V/ $SiO_{2(700)}$ -O₂ and V/TMS-SiO₂₍₇₀₀₎-O₂ are shown in Figure 7. A single isotropic shift is observed at -694 ppm for both samples. This indicates the formation of similar vanadium species in both materials, albeit at a different surface densities. The very intense spinning sidebands point toward a nondynamic chemical environment for these sites, which precludes a dynamic averaging of the local environment of the ⁵¹V nucleus and leads to the inhomogeneously broadened peaks observed in the spectrum. We therefore attribute this signal to a tetrahedral VO₄ species with three Si–O–V linkages to the silica surface and one single V=O group (proposed structure inset in Figure 7). Previous work by Baiker and co-workers on vanadium oxide/silica materials assigns ⁵¹V NMR shifts for monomeric tetrahedral VO₄ species to an isotropic shift at ca. -715 ppm, and distorted tetrahedral VO₄ sites at ca. -691 ppm.¹⁸ We would expect the observed shift at -694 ppm for V/SiO₂₍₇₀₀₎- O_2 and V/TMS-SiO₂₍₇₀₀₎-O₂ to have a distorted tetrahedral geometry as well, due to the amorphous nature of the silica support. As a comparison, we also measured the ⁵¹V MAS NMR isotropic shift of tris(triphenylsiloxy) vanadium oxide $(VO(OSiPh_3)_3)$, to be -720 ppm (Figure 7 inset, spectrum in Figure S4), in order to replicate a previous study on model compounds for silica-supported vanadium oxide.⁹ The chemical shift observed for V/SiO₂₍₇₀₀₎-O₂ and reference compound $VO(OSiPh_3)_3$, in combination with previous literature^{9,15,18} appears to indicate clearly the presence of solely isolated VO₄ species with bonds only to the silica surface, and no oligomeric species with V-O-V linkages. These structural assignments were also verified by analysis of the pre-edge peak in the vanadium K-edge XANES spectra (Figure S2, panel b) for V/ SiO₂₍₇₀₀₎-O₂ and V/TMS-SiO₂₍₇₀₀₎-O₂. The normalized preedge peak intensity for the tetrahedral, four-fold oxygen



Scheme 3. Proposed Reconstruction Pathway for Vanadium Sites on V/SiO₂₍₇₀₀₎ upon Calcination^a

^{*a*}Various bonds and molecules are highlighted to indicate the experiment from which they were initially observed (see legend in figure). Based on *in situ* DRIFTS, TGA-DSC-MS, and Raman studies the restructuring process involves (a) the elimination of alkoxide ligands in the form of propene from both (i) $V-O-^{i}Pr$ and (ii) Si $-O-^{i}Pr$ moieties, and (b) the formation of multipodal species on the silica surface by reaction of V- OH groups with silanol groups generated during calcination. It is important to note that processes (a) and (b) do not occur consecutively, but rather in concert with one another as suggested by TGA-DSC-MS and DRIFTS.



Figure 7. ⁵¹V MAS NMR spectra of calcined materials $V/SiO_{2(700)}$ -O₂ (top) and V/TMS-SiO₂₍₇₀₀₎-O₂ (bottom) All calcinations were done at 600 °C in air. Prior to NMR analysis, samples were dehydrated at 300 °C under vacuum to remove any physisorbed water. Inset structures correspond to the assignment of the single isotropic shift observed in both spectra (left) and the reference material for tetrahedrally coordinated vanadium species and its associated chemical shift (right).

coordinated VO(OSiPh₃)₃ reference, V/SiO₂₍₇₀₀₎-O₂ and V/ TMS-SiO₂₍₇₀₀₎-O₂ materials are all nearly identical, which is indicative of similar local coordination environments for each material. On the basis of these NMR and XANES data for V/ SiO₂₍₇₀₀₎-O₂ and V/TMS-SiO₂₍₇₀₀₎-O₂, we also conclude that the calcined surface species that arise from the initial reaction of VO(OⁱPr)₃ with both silanols and strained siloxane bridges result in structurally similar surface species.

Oxidative Dehydrogenation of Propane as Catalytic Test Reaction. The oxidative dehydrogenaton of propane (ODHP) is a structure-sensitive reaction. Indeed, it is well established in the literature that consecutive overoxidation of the desired propylene is enhanced by the presence of three-dimensional V_2O_5 particles.^{1,4} When comparing the performance of our V/SiO₂₍₇₀₀₎-O₂ material with an analogous material obtained via incipient wetness impregnation featuring the same vanadium loading (as well as the same vanadium coverage

nm⁻²), very similar turnover frequencies were obtained: 0.0145 and 0.0163 s⁻¹, respectively, at 490 °C. Also, propene selectivity at a given propane conversion for dispersed vanadium oxide prepared by grafting and incipient wetness impregnation is in perfect agreement (Figure S5).⁴² We interpret these observations as complementary catalytic evidence for the fact that we obtained solely two-dimensional VO_X surface species, and that analogous sites are formed irrespective of the synthesis procedure.

CONCLUSIONS

In this contribution, we use grafting as a tool to understand the key chemical reactions that occur during (i) the anchoring of $VO(O'Pr)_3$ to dehydrated silica, as well as (ii) the calcination of the material to form supported metal oxide sites. When $VO(O'Pr)_3$ is grafted to $SiO_{2(700)}$, it reacts with both isolated silanols and strained siloxane bridges, as determined through a combination of ICP and transmission FT-IR analyses. The uncalcined material has two distinct surface sites as determined by ¹³C and ⁵¹V MAS NMR and verified by XANES. In situ DRIFTS, TGA-DSC-MS, and Raman studies on the calcination of V/SiO₂₍₇₀₀₎ reveal the elimination of isopropoxide ligands as propene to form transient V-OH species, which then react with the silica surface to form isolated, tetrahedral VO₄ sites. ⁵¹V MAS NMR of the calcined silvlated and nonsilvlated materials shows that both original vanadium species observed in the ⁵¹V MAS NMR spectra result in the formation of similar surface sites after calcination.

The methodology used for the V/SiO₂₍₇₀₀₎ system can be extended toward a more generalized understanding of surface species that arise from grafting with molecular precursors. An increased understanding of the surface reactions that occur at the molecular level of these supported materials can open avenues for new strategies for enhanced dispersion of desired two-dimensional metal or metal oxide sites on a support material.

Supporting Information

The Supporting Information is available free of charge on the ACS Publications website at DOI: 10.1021/acs.chemma-ter.6b02118.

Simulated ⁵¹V MAS NMR spectrum, XANES data, deconvolution of DRIFTS data, ⁵¹V NMR spectrum for VO(SiOPh₃)₃, ODHP activity data, table of fitting parameters from simulated ⁵¹V NMR spectra, table of BET surface area and vanadium ICP data (PDF).

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Notes

The authors declare no competing financial interest.

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